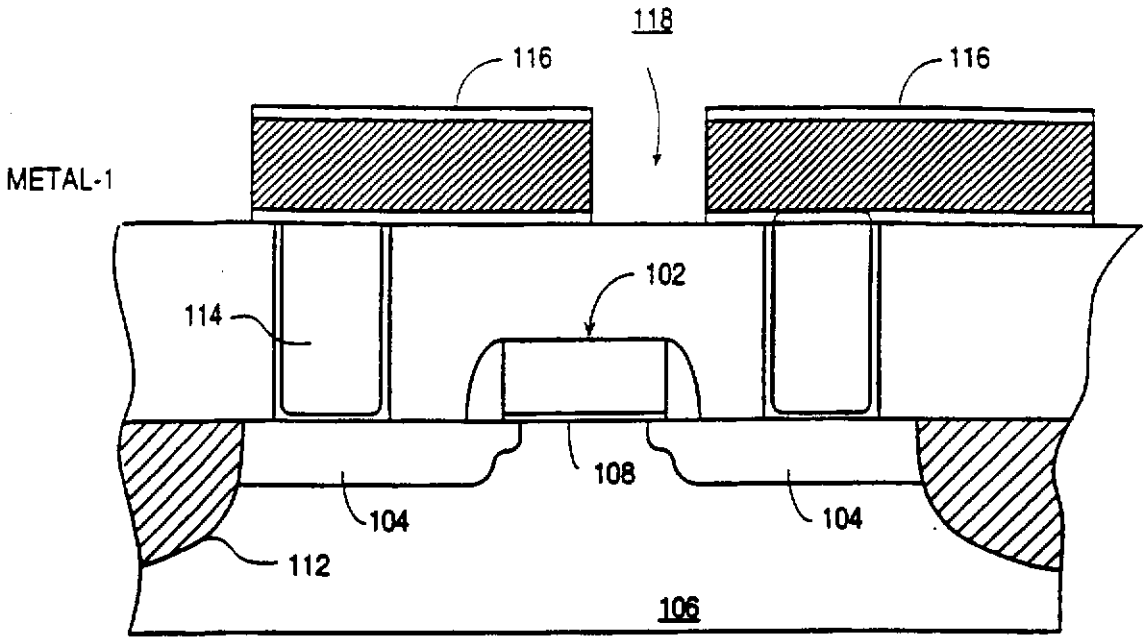

118
116
116
METAL-1
102
114
108
104
104
112
106

FIG. 1

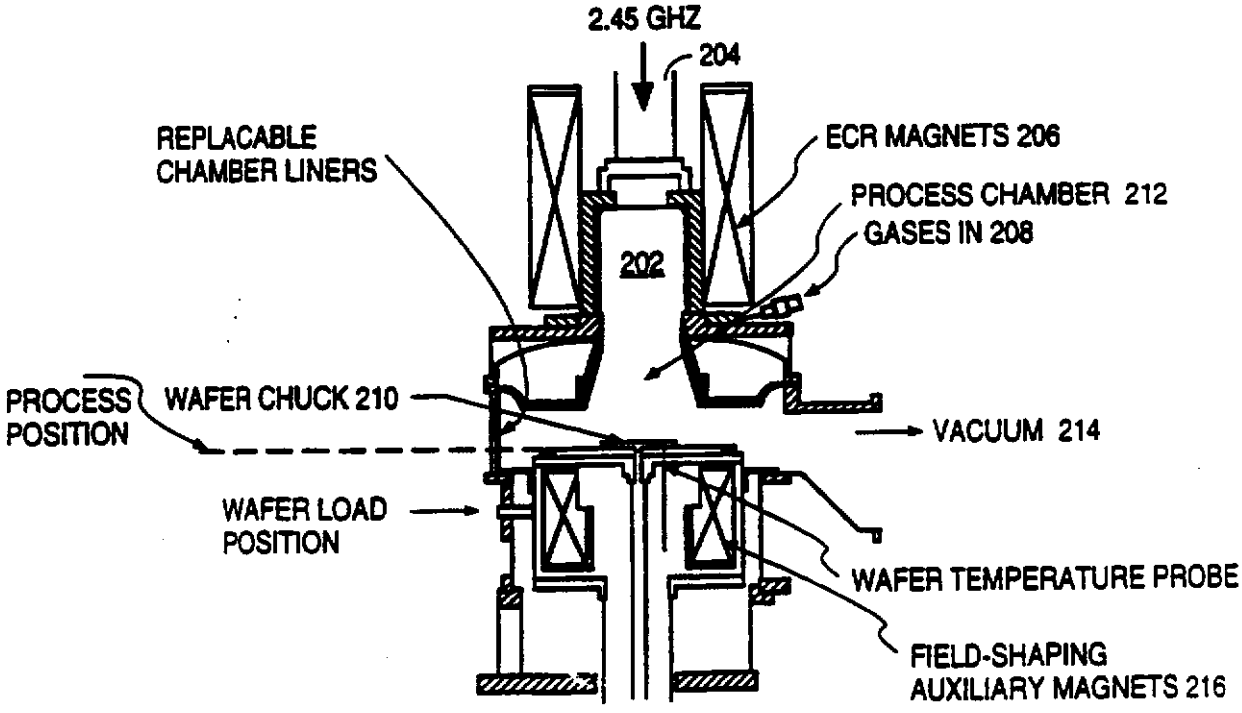

2.45 GHZ
204
REPLACABLE
CHAMBER LINERS
ECR MAGNETS 206
PROCESS CHAMBER 212
GASES IN 208
202
PROCESS
POSITION
WAFER CHUCK 210
VACUUM 214
WAFER LOAD
POSITION
WAFER TEMPERATURE PROBE
FIELD-SHAPING
AUXILIARY MAGNETS 216

FIG. 2

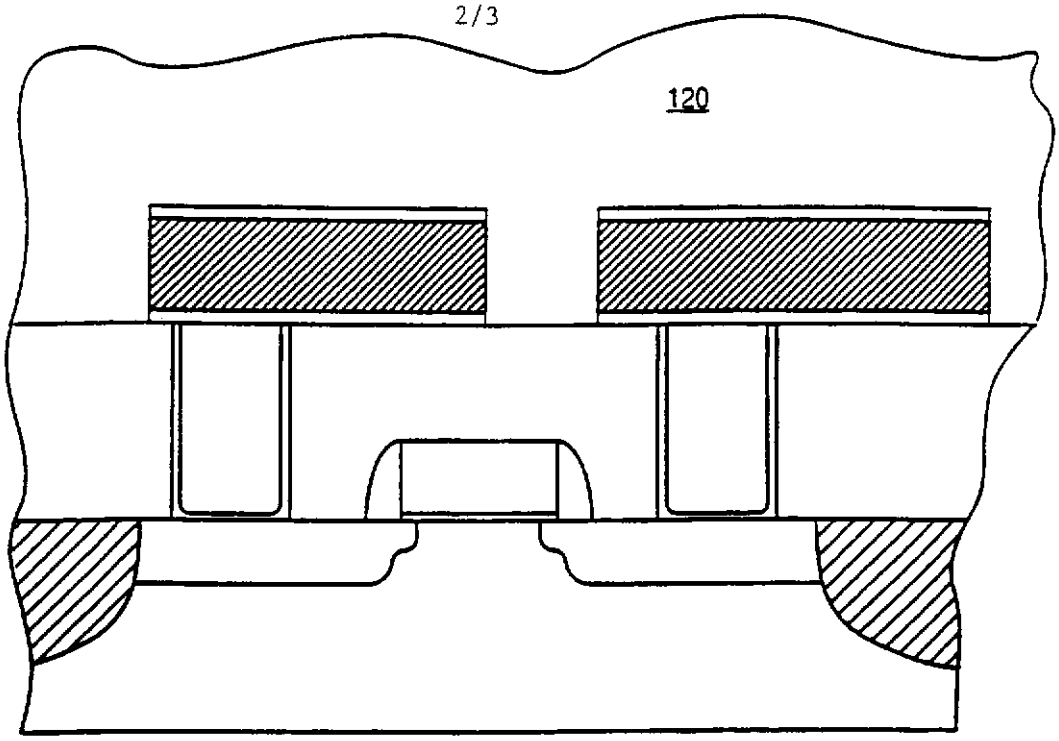


FIG. 3

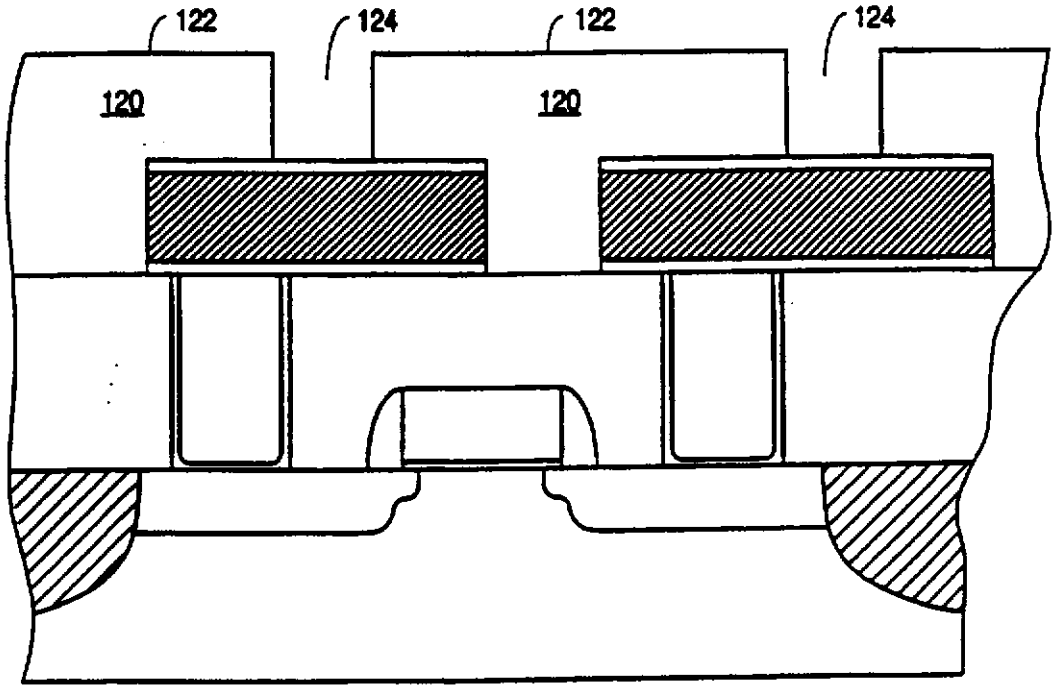


FIG. 4

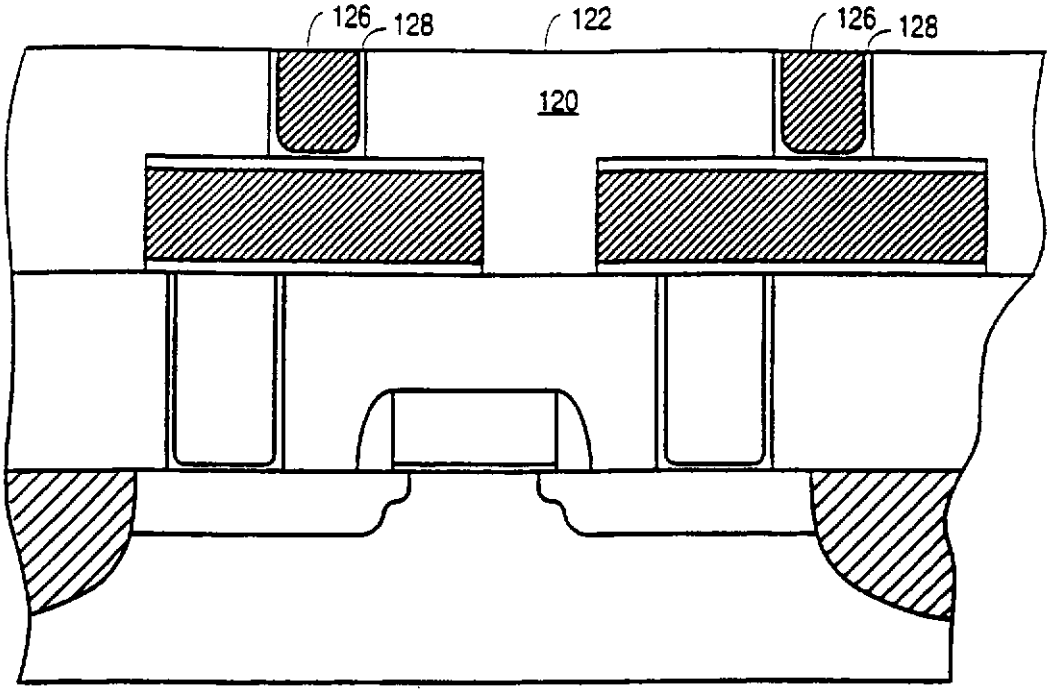

126
128
122
126
128
120

FIG. 5

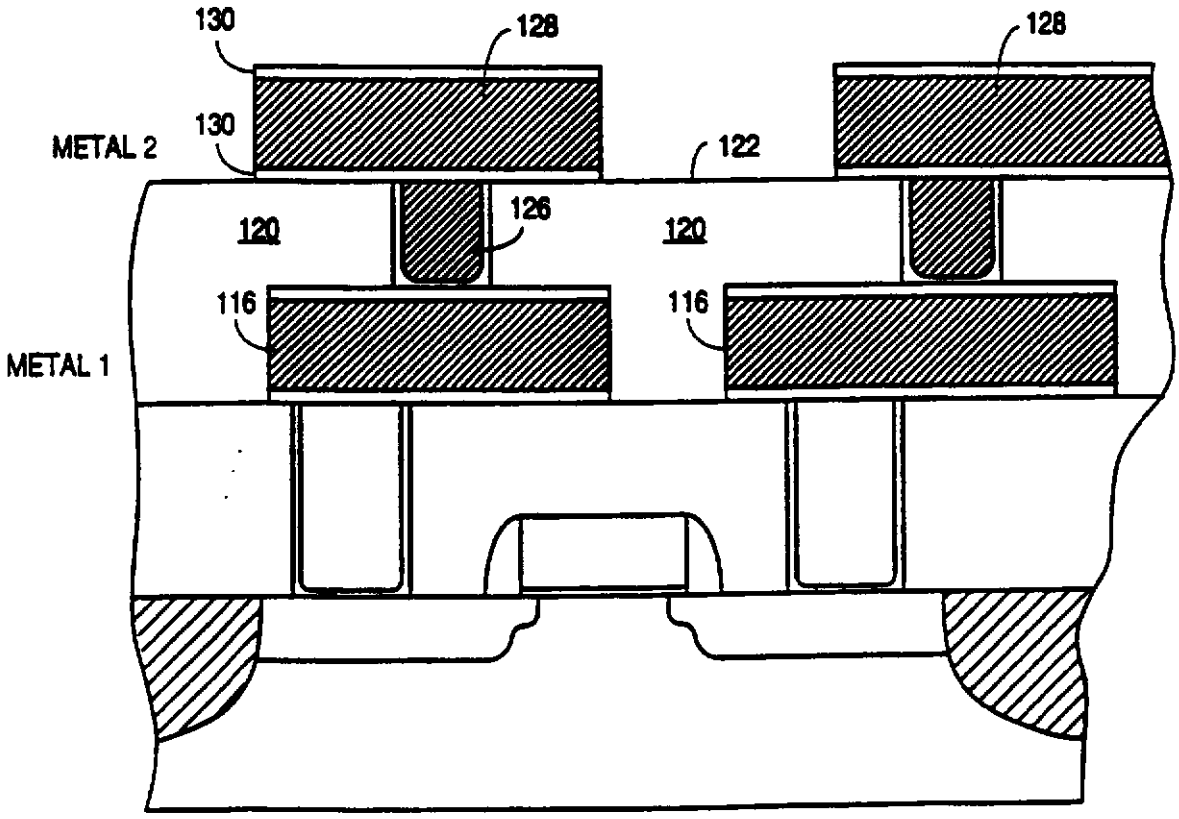

130
128
128
METAL 2
130
122
120
126
120
116
116
METAL 1

FIG. 6